

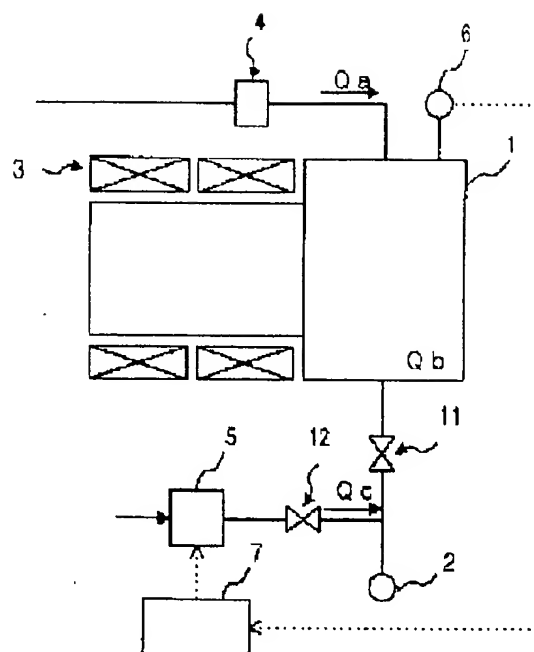
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APPLICANT : SHIMADZU CORP;

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INT.CL. : C23C 16/44 H01L 21/205

TITLE : FILM FORMING DEVICE



ABSTRACT : PROBLEM TO BE SOLVED: To execute the control of pressure without reducing the purity of a process gas in a film forming device.

SOLUTION: The space between the intake part of an exhaust pump (turbo- molecular pump 2) executing the exhaust in a process chamber 1 and the exhaust part of the process chamber 1 is provided with gas introducing parts 5 and 6 capable of controlling the flow rate of gas, and the gas introducing parts 5 and 6 execute the control of the flow rate of gas in accordance with the pressure in the process chamber 1, by which the control of the pressure in the process chamber 1 is executed. When the pressure in the process chamber 1 changes, the gas introducing parts 5 and 6 control the flow rate of the gas to be introduced in accordance with the change of the pressure to reduce the partial pressure of the released gas in the process chamber 1, and moreover, the exhausting speed of the exhaust pump is substantially regulated to control the pressure in the process chamber 1 to the set pressure.

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